

Confirmation No. 6408

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Meunier-Beillard <i>et al.</i>	Examiner:	Khiem Nguyen
Serial No.:	10/550,853	Group Art Unit:	2823
Filed:	September 22, 2005	Docket No.:	NL030357 US1 (NXPS.265PA)
Title:	METHOD OF EPITAXIAL DEPOSITION OF AN N-DOPED SILICON LAYER		

AMENDMENT AND RESPONSE TO RESTRICTION/ELECTION REQUIREMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Customer No.
65913

Dear Sir:

This communication is in reply to the Office Action dated April 17, 2009, in which a restriction/election requirement was presented. In response thereto, Applicant elects claims 1-14 identified under Group I with traverse.

A complete listing of the Claims, to include amendments thereto, and Remarks follow.